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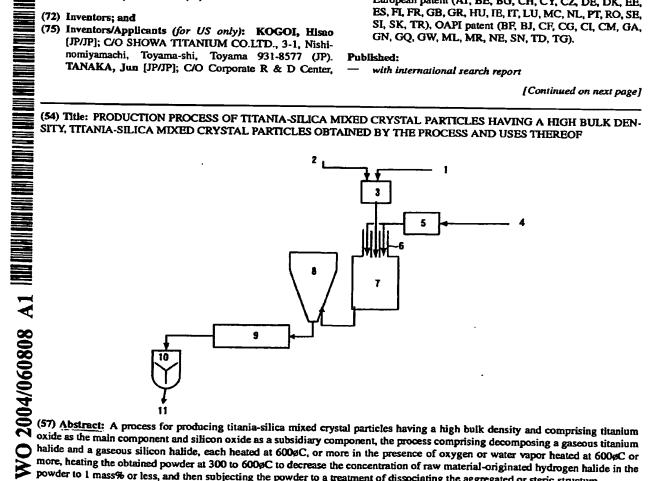
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halide and a gaseous silicon halide, each heated at 600¢C, or more in the presence of oxygen or water vapor heated at 600¢C or more, heating the obtained powder at 300 to 600¢C to decrease the concentration of raw material-originated hydrogen halide in the powder to 1 mass% or less, and then subjecting the powder to a treatment of dissociating the aggregated or steric structure.